			\leftarrow
	Application No.	Applicant(s)	
Notice of Allowability	10/796,587	NAIINI ET AL.	
	Examiner	Art Unit	
	John S. Chu	1752	
The MAILING DATE of this communication apperature All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in or other appropriate commu IGHTS. This application is s	this application. If not include inication will be mailed in due	d course, THIS
1. A This communication is responsive to <u>12/7/05</u> .			
2. The allowed claim(s) is/are <u>1-79</u> .		,	
 3. ☐ Acknowledgment is made of a claim for foreign priority ur a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 		or (f).	
Certified copies of the priority documents have		n No	
Copies of the certified copies of the priority documents have			: a = far Ab -
International Bureau (PCT Rule 17.2(a)).	cuments have been received	i iii uiis national stage applicat	ion from the
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file IENT of this application.	a reply complying with the req	uirements
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give	itted. Note the attached EXA	MINER'S AMENDMENT or No declaration is deficient.	OTICE OF
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.	,	
(a) including changes required by the Notice of Draftspers		(PTO-948) attached	
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date		,	
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or	in the Office action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on th he header according to 37 CF	e drawings in the front (not the R 1.121(d).	back) of
 DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT 	sit of BIOLOGICAL MATE FOR THE DEPOSIT OF BIO	ERIAL must be submitted. No DECITE MATERIAL.	ote the
	·		
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5 Notice of Inf	ormal Patent Application (PTC	152)
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)		orman Patent Application (PTC) immary (PTO-413),	- 132)
	Paper No./I	Mail Date 12/7/05.	
 Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 	8), 7. 🗌 Examiner's A	Amendment/Comment	
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. 🛭 Examiner's	Statement of Reasons for Allov	wance
	9.		

Art Unit: 1752

REASONS FOR ALLOWANCE

- 1. The following is an examiner's statement of reasons for allowance: The claimed invention is drawn to the following:
 - 1. (Original) A polybenzoxazole precursor polymer with Structure I

wherein Ar¹ is selected from the group consisting of a tetravalent aromatic group, a tetravalent heterocyclic group and mixtures thereof; Ar² is selected from the group consisting of a divalent aromatic, a divalent heterocyclic, a divalent alicyclic and a divalent aliphatic group that may contain silicon; Ar³ is selected from the group consisting of a divalent aromatic group, a divalent aliphatic group, a divalent heterocyclic group and mixtures thereof; Ar⁴ is selected from the group consisting of Ar¹ (OH)₂ and Ar², x is from about 10 to about 1000; y is from 0 to about 900; D is selected from the group consisting of one of the following moieties IIa-IIe:

$$\begin{array}{c} O \\ O_2 \\ O_2 \\ O_3 \\ O_4 \\ O_2 \\ O_2 \\ O_2 \\ O_3 \\ O_2 \\ O_4 \\ O_2 \\ O_2 \\ O_3 \\ O_4 \\ O_4 \\ O_4 \\ O_4 \\ O_5 \\ O_6 \\ O_7 \\ O_8 \\ O$$

- 12. (Currently amended) A positive photosensitive resin composition comprising:
 - (a) at least one polybenzoxazole precursor polymer selected from the group consisting of polymers having Structure I and III;

Art Unit: 1752

wherein Ar1 is selected from the group consisting of a tetravalent aromatic group, a tetravalent heterocyclic group and mixtures thereof; Ar2 is selected from the group consisting of a divalent aromatic, a divalent heterocyclic, a divalent alicyclic and a divalent aliphatic group that may contain silicon and mixtures thereof; Ar3 is selected from the group consisting of a divalent aromatic group, a divalent aliphatic group, a divalent heterocyclic group and mixtures thereof; Ar4 is selected from the group consisting of Ar1 (OH)₂ and Ar², D is selected from the group consisting of one of the following moieties llalle:

(IId)

Art Unit: 1752

wherein, R is selected from the group consisting of H, a $C_1 - C_4$ alkyl group, a $C_1 - C_4$ alkoxy group and a cyclohexyl group; k^1 can be any positive value of up to about 0.5, k^2 can be any value from about 1.5 to 2 with the proviso that $(k^1+k^2)=2$, x is from about 10 to about 1000; y is from about 0 to about 900; and G is an organic group having a carbonyl, carbonyloxy or sulfonyl group attached directly to the terminal NH of the polymer,

(b) at least one non-polymeric photosensitive compound comprising a compound having within its structure one or more of moieties selected from the group consisting of IIa-IIe, with the proviso that if a polymer of Structure III is the sole polybenzoxazole precursor polymer, the non-polymeric photosensitive compound is selected from the group consisting of compounds described by structures IV—VI V-VI,

$$(QO)_{g}$$

$$R^{1}$$

$$R^{2}$$

$$R^{3}$$

$$(PA)$$

$$(PA)$$

$$(QO)_{g}$$

$$R^{2}$$

$$R^{3}$$

$$(QO)_{g}$$

$$R^{4}$$

$$R^{3}$$

$$(QO)_{g}$$

$$R^{3}$$

$$(QO)_{g}$$

$$R^{3}$$

$$(QO)_{g}$$

wherein R1, R2, R4, R5, R6 and R7 each independently are selected from the group

Application/Control Number: 10/796,587

Art Unit: 1752

consisting of a linear or branched C_1 - C_4 alkyl group, a phenyl or halide substituted C_1 - C_4 linear or branched alkyl group, a perfluorinated C_1 - C_4 linear or branched alkyl group, a C_5 - C_7 cycloalkyl group, a C_1 - C_4 alkyl or halide substituted C_5 - C_7 cycloalkyl group, or alternatively R^1 and R^2 or any two of R^4 , R^5 , and R^6 may together form a 5-7 membered ring; each R^3 is independently selected from the group consisting of H, a linear or branched C_1 - C_4 alkyl group, a phenyl or halide substituted C_1 - C_4 linear or branched alkyl group, a perfluorinated linear or branched C_1 - C_4 alkyl group, a C_5 - C_7 cycloalkyl group, a C_1 - C_4 alkyl or halide substituted C_5 - C_7 cycloalkyl group, an unsubstituted phenyl group, and a phenyl or alkyl or halide substituted phenyl group; Q is selected from the group consisting of H or D with the proviso that at least one Q = D; D is selected from the group consisting of one of the moieties IIa-IIe; a is an integer from 1 to 5; b and c are integers from 0 to 5 with the provisos: (1) that for Structure IV, if a = b = 1 and both OQ are substituted para to the R^3 cubstituent, then both R^4 and R^2 are not simultaneously methyl, and (2) 1 <= a+b < 6; and the proviso that for Structure VI, if a = b = c = 1 and all OQ are para to the triphenyl methane carbon substituent, then at least one R^3 is not H; and

(c) at least one solvent.

Claims 23, 26, 29, 30, 37, 43 and 54 are objected to under 37 CFR 1.75(c), previously objected to is now being seen as definite and clear and the objection is **withdrawn**.

The rejection under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention is also **withdrawn** based on the discussion during the telephonic interview (see attached PTOL-413).

None of the prior art references of record disclose the recited end-capped polybenzoxazole precursor having the formula of structure I having photosensitive groups defined as D condensed at the hydroxyl position in a composition with a photosensitive compound (b) and a solvent (c). The claims further define the preferred photosensitive naphthoquinone diazide compound for component (b) to have a phenolic backbone structure of formula V and VI as seen in claim 12. The closest prior art reference made of record is to TAKAHASHI et al (6,376,151) which discloses the use of the following compound having the

structure of the photosensitive component. Here applicants have defined the difference between the interpretation of an alkyl substituted phenylene which was the interpretation by the Office from the claimed phenyl substituted alkyl group defined for variable R⁵. The examiner concurs with the definition and interpretation as described by applicant in the Remarks of October 31, 2005, pp. 2-5.

Page 6

Because none of the prior art references of record anticipate or render obvious the claimed invention, all the claims, claims 1-79 are seen as allowable and passed to issue.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

The fax phone number for the USPTO is (571) 273-8300.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Group receptionist whose telephone number is (571) 272-1700.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PMR only. For more information about the PAIR

Application/Control Number: 10/796,587

Art Unit: 1752

Page 7

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

John S. Chu

Primary Examiner, Group 1700

J.Chu December 7, 2005